

## Publikationen

- (2014): Dielectric Material Options for Integrated Capacitors. In: ECS Journal of Solid State Science and Technology, vol. 3, no. 8. DOI: 10.1149/2.0101408jss.
- (2013): Properties of stacked SrTiO<sub>3</sub>/Al<sub>2</sub>O<sub>3</sub> metal-insulator-metal capacitors. In: Journal of Vacuum Science & Technology B, vol. 31, no. 1. DOI: 10.1116/1.4766183.
- (2012): Metal-Insulator-Metal capacitors with ALD grown SrTiO<sub>3</sub>: Influence of Pt electrodes. In: IOP Conference Series: Materials Science and Engineering, vol. 41.
- (2012): Electrical and Morphological Properties of ALD and AVD Grown Perovskite-Type Dielectrics and Their Stacks for Metal-Insulator-Metal Applications. In: ECS Journal of Solid State Science and Technology, vol. 1, no. 1.
- (2012): Properties of atomic-vapor and atomic-layer deposited Sr, Ti, and Nb doped Ta<sub>2</sub>O<sub>5</sub> Metal-Insulator-Metal capacitors. In: Thin Solid Films, vol. 520, no. 14, pp. 4576-4579. DOI: 10.1016/j.tsf.2011.10.199.
- (2011): ALD and AVD Grown Perovskite-type Dielectrics for Metal-Insulator-Metal Application. (Invited). In: ECS Transactions (The Electrochemical Society), vol. 41, no. 2, pp. 53-61. DOI: 10.1149/1.3633654.
- (2011): ALD grown NbTaO<sub>x</sub> based MIM capacitors. In: Microelectronic Engineering, vol. 88, no. 8, pp. 2447-2451.
- (2011): Single SrTiO<sub>3</sub> and Al<sub>2</sub>O<sub>3</sub>/SrTiO<sub>3</sub>/Al<sub>2</sub>O<sub>3</sub> based MIM capacitors: Impact of the bottom electrode material. In: Microelectronic Engineering, vol. 88, no. 7, pp. 1521-1524. DOI: 10.1016/j.mee.2011.03.022.
- (2011): Enhanced leakage current behavior of Sr<sub>2</sub>Ta<sub>2</sub>O<sub>7-x</sub>/SrTiO<sub>3</sub> bilayer dielectrics for metal-insulator-metal capacitors. In: Thin Solid Films, vol. 519, no. 17, pp. 5734-5739. DOI: 10.1016/j.tsf.2011.01.001.